

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	3586	((568/659) or (568/660) or (568/661) or (568/662) or (568/663) or (568/811) or (568/812) or (568/813) or (568/814) or (556/9) or (556/12)). CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2005/02/18 13:10
L2	1827283	copper or iron or cobalt or nickel or rhodium or palladium or ruthenium or platinum	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:10
L3	1443	I1 and I2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:11
L4	56063	phosphine	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:11
L5	314	I3 and I4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:11
L6	206666	(sodium near2 carbonate) or (potassium near2 carbonate)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:12
L7	73	I5 and I6	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:30
L8	337878	styrene or vinylbenzene or phenylethylene or cinnamene	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:32
L9	351	I3 and I8	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:32

L10	335	I9 not I7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:36
L11	55	I6 and I10	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:41
L12	27028	sumida.in. or kume.in. or koga.in. or komoriya.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:42
L13	341	I8 and I12	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	ON	2005/02/18 13:42

10/600,510

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Welcome to STN International! Enter x:x

LOGINID:SSSPTA1204RXW

PASSWORD:

TERMINAL (ENTER 1, 2, 3, OR ?):2

* * * * * Welcome to STN International * * * * *

NEWS	1		Web Page URLs for STN Seminar Schedule - N. America
NEWS	2		"Ask CAS" for self-help around the clock
NEWS	3	SEP 01	New pricing for the Save Answers for SciFinder Wizard within STN Express with Discover!
NEWS	4	OCT 28	KOREAPAT now available on STN
NEWS	5	NOV 30	PHAR reloaded with additional data
NEWS	6	DEC 01	LISA now available on STN
NEWS	7	DEC 09	12 databases to be removed from STN on December 31, 2004
NEWS	8	DEC 15	MEDLINE update schedule for December 2004
NEWS	9	DEC 17	ELCOM reloaded; updating to resume; current-awareness alerts (SDIs) affected
NEWS	10	DEC 17	COMPUAB reloaded; updating to resume; current-awareness alerts (SDIs) affected
NEWS	11	DEC 17	SOLIDSTATE reloaded; updating to resume; current-awareness alerts (SDIs) affected
NEWS	12	DEC 17	CERAB reloaded; updating to resume; current-awareness alerts (SDIs) affected
NEWS	13	DEC 17	THREE NEW FIELDS ADDED TO IFIPAT/IFIUDE/IFICDB
NEWS	14	DEC 30	EPFULL: New patent full text database to be available on STN
NEWS	15	DEC 30	CAPLUS - PATENT COVERAGE EXPANDED
NEWS	16	JAN 03	No connect-hour charges in EPFULL during January and February 2005
NEWS	17	JAN 26	CA/CAPLUS - Expanded patent coverage to include the Russian Agency for Patents and Trademarks (ROSPATENT)
NEWS	18	FEB 10	STN Patent Forums to be held in March 2005
NEWS	19	FEB 16	STN User Update to be held in conjunction with the 229th ACS National Meeting on March 13, 2005
NEWS EXPRESS			JANUARY 10 CURRENT WINDOWS VERSION IS V7.01a, CURRENT MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP), AND CURRENT DISCOVER FILE IS DATED 10 JANUARY 2005
NEWS HOURS			STN Operating Hours Plus Help Desk Availability
NEWS INTER			General Internet Information
NEWS LOGIN			Welcome Banner and News Items
NEWS PHONE			Direct Dial and Telecommunication Network Access to STN
NEWS WWW			CAS World Wide Web Site (general information)

Enter NEWS followed by the item number or name to see news on that specific topic.

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10/600,510

* * * * * STN Columbus * * * * *

FILE 'HOME' ENTERED AT 14:07:10 ON 18 FEB 2005

=> FIL STNGUIDE

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

0.21

0.21

FILE 'STNGUIDE' ENTERED AT 14:07:26 ON 18 FEB 2005

USE IS SUBJECT TO THE TERMS OF YOUR CUSTOMER AGREEMENT

COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY, JAPAN SCIENCE

AND TECHNOLOGY CORPORATION, AND FACHINFORMATIONSZENTRUM KARLSRUHE

FILE CONTAINS CURRENT INFORMATION.

LAST RELOADED: Feb 11, 2005 (20050211/UP).

=> file reg

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

0.06

0.27

FILE 'REGISTRY' ENTERED AT 14:07:46 ON 18 FEB 2005

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Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 16 FEB 2005 HIGHEST RN 832673-31-1

DICTIONARY FILE UPDATES: 16 FEB 2005 HIGHEST RN 832673-31-1

TSCA INFORMATION NOW CURRENT THROUGH JANUARY 18, 2005

Please note that search-term pricing does apply when conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

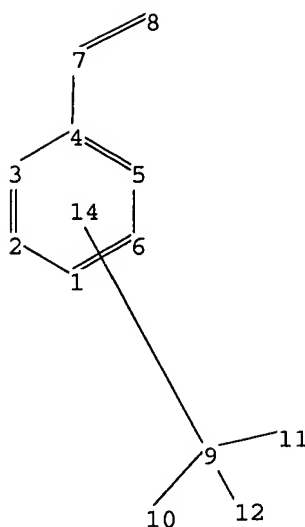
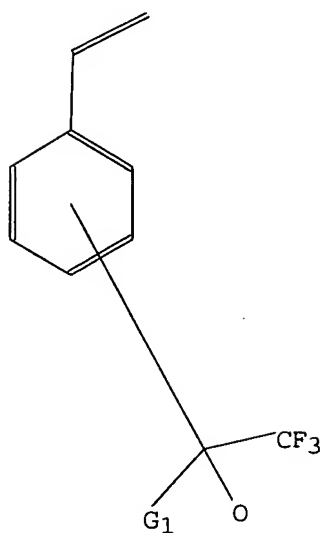
Experimental and calculated property data are now available. For more information enter HELP PROP at an arrow prompt in the file or refer to the file summary sheet on the web at:

<http://www.cas.org/ONLINE/DBSS/registryss.html>

=>

Uploading C:\Program Files\Stnexp\Queries\10600510.str

10/600,510



chain nodes :
7 8 9 10 11 12
ring nodes :
1 2 3 4 5 6
chain bonds :
4-7 7-8 9-12 9-10 9-11
ring bonds :
1-2 1-6 2-3 3-4 4-5 5-6
exact/norm bonds :
9-12 9-10
exact bonds :
4-7 7-8 9-11
normalized bonds :
1-2 1-6 2-3 3-4 4-5 5-6
isolated ring systems :
containing 1 :

G1:CH3,CF3

Match level :

1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:Atom 7:CLASS 8:CLASS 9:CLASS 10:CLASS
11:CLASS 12:CLASS 14:CLASS

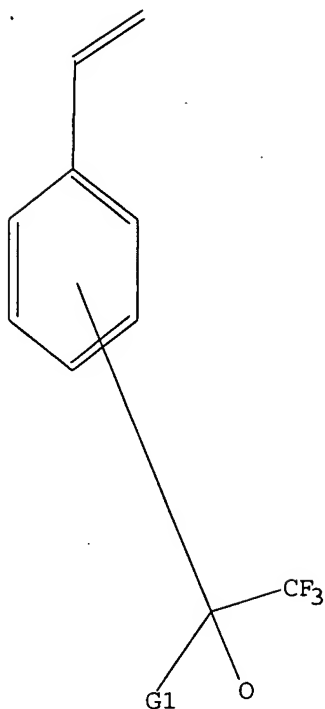
L1 STRUCTURE UPLOADED

=> d

L1 HAS NO ANSWERS

L1 STR

10/600,510



G1 Me,CF3

Structure attributes must be viewed using STN Express query preparation.

=> s l1

SAMPLE SEARCH INITIATED 14:08:23 FILE 'REGISTRY'
SAMPLE SCREEN SEARCH COMPLETED - 1297 TO ITERATE

77.1% PROCESSED 1000 ITERATIONS
INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)
SEARCH TIME: 00.00.01

29 ANSWERS

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 23780 TO 28100
PROJECTED ANSWERS: 385 TO 1119

L2 29 SEA SSS SAM L1

=> s l1 ful

FULL SEARCH INITIATED 14:08:52 FILE 'REGISTRY'
FULL SCREEN SEARCH COMPLETED - 26059 TO ITERATE

100.0% PROCESSED 26059 ITERATIONS
SEARCH TIME: 00.00.01

669 ANSWERS

L3 669 SEA SSS FUL L1

=> d scan

L3 669 ANSWERS REGISTRY COPYRIGHT 2005 ACS on STN
IN Carbonic acid, 1,1-dimethylethyl 1-[4-ethenyl-2-(trifluoromethyl)phenyl]-
2,2,2-trifluoro-1-(trifluoromethyl)ethyl ester, polymer with

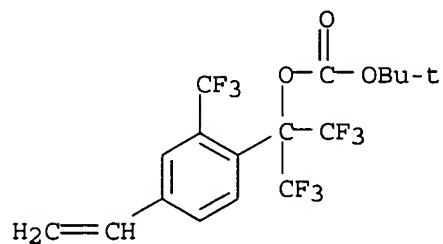
10/600,510

1-(1,1-dimethylethoxy)-4-ethenylbenzene and 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol (9CI)

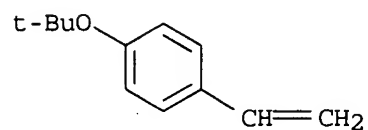
MF (C17 H15 F9 O3 . C12 H16 O . C11 H8 F6 O)x

CI PMS

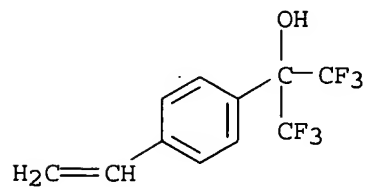
CM 1



CM 2



CM 3



HOW MANY MORE ANSWERS DO YOU WISH TO SCAN? (1):0

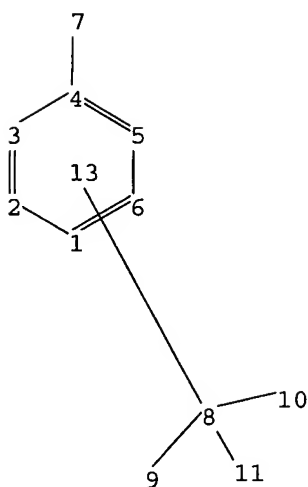
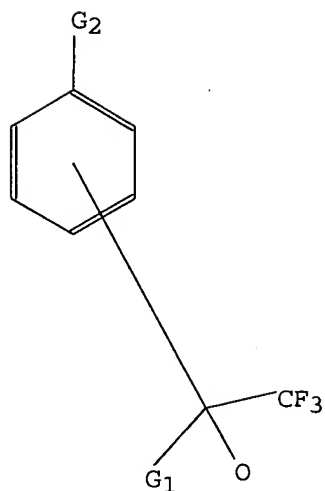
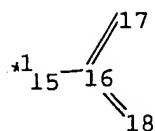
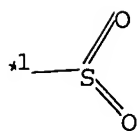
=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=>

Uploading C:\Program Files\Stnexp\Queries\10600510a.str

10/600,510



chain nodes :
7 8 9 10 11 15 16 17 18
ring nodes :
1 2 3 4 5 6
chain bonds :
4-7 8-11 8-9 8-10 15-16 16-17 16-18
ring bonds :
1-2 1-6 2-3 3-4 4-5 5-6
exact/norm bonds :
4-7 8-11 8-9 15-16 16-17 16-18
exact bonds :
8-10
normalized bonds :
1-2 1-6 2-3 3-4 4-5 5-6
isolated ring systems :
containing 1 :

G1:CH3,CF3

G2:X, [*1]

Match level :

1:Atom 2:Atom 3:Atom 4:Atom 5:Atom 6:Atom 7:CLASS 8:CLASS 9:CLASS 10:CLASS
11:CLASS 13:CLASS 15:CLASS 16:CLASS 17:CLASS 18:CLASS

L4 STRUCTURE UPLOADED

=> que L4

10/600,510

L5 QUE L4

=> d

L5 HAS NO ANSWERS

L4 STR

* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT *

Structure attributes must be viewed using STN Express query preparation.

L5 QUE L4

=> s 15

SAMPLE SEARCH INITIATED 14:10:16 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 542 TO ITERATE

100.0% PROCESSED 542 ITERATIONS

23 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH **COMPLETE**

PROJECTED ITERATIONS: 9444 TO 12236

PROJECTED ANSWERS: 172 TO 746

L6 23 SEA SSS SAM L4

=> s 15 ful

FULL SEARCH INITIATED 14:10:22 FILE 'REGISTRY'

FULL SCREEN SEARCH COMPLETED - 10993 TO ITERATE

100.0% PROCESSED 10993 ITERATIONS

345 ANSWERS

SEARCH TIME: 00.00.01

L7 345 SEA SSS FUL L4

=> file caplus

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

323.95

324.22

FILE 'CAPLUS' ENTERED AT 14:10:45 ON 18 FEB 2005

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FILE COVERS 1907 - 18 Feb 2005 VOL 142 ISS 9

FILE LAST UPDATED: 17 Feb 2005 (20050217/ED)

This file contains CAS Registry Numbers for easy and accurate substance identification.

10/600,510

=> s 13 and 17

.255 L3

170 L7

L8 12 L3 AND L7

=> dup rem 18

PROCESSING COMPLETED FOR L8

L9 12 DUP REM L8 (0 DUPLICATES REMOVED)

=> d 1-12 ti

L9 ANSWER 1 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Process for producing fluorine-containing, polymerizable styrene monomer and intermediates used in same

L9 ANSWER 2 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Photosensitive resin composition

L9 ANSWER 3 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Photosensitive resin composition

L9 ANSWER 4 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Photosensitive resin composition for photolithography

L9 ANSWER 5 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Positive-working photoresist composition containing fluoro-substituted nitrogen compound

L9 ANSWER 6 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Vacuum UV-sensitive resin composition containing ionic compound reactive towards acid

L9 ANSWER 7 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Positive-working vacuum UV-sensitive photoresist material composition containing specific resin

L9 ANSWER 8 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Positive-working resist composition containing specific fluorine group-containing resin

L9 ANSWER 9 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Positive resist composition

L9 ANSWER 10 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Polymers with fluorinated styrene-based mer units, their positive resist materials, and their patterning

L9 ANSWER 11 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI Sulfonic acid esters, their production and photosensitive compositions containing them.

L9 ANSWER 12 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

TI The synthesis and attempted polymerization of an α,β,β -trifluorostyrene disubstituted by hexafluoro-2-propyl groups

=> d 1-12 bib fhitr

L9 ANSWER 1 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:3703 CAPLUS

DN 140:60144

10/600,510

TI Process for producing fluorine-containing, polymerizable styrene monomer
and intermediates used in same
IN Sumida, Shinichi; Kume, Takashi; Koga, Sunao; Komoriya, Haruhiko
PA Central Glass Company, Limited, Japan
SO U.S. Pat. Appl. Publ., 16 pp.

CODEN: USXXCO

DT Patent

LA English

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 2004002612	A1	20040101	US 2003-600510	20030623
	JP 2004026691	A2	20040129	JP 2002-183138	20020624
PRAI	JP 2002-183138	A	20020624		

OS MARPAT 140:60144

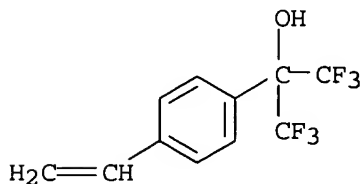
IT **2386-82-5P**

RL: IMF (Industrial manufacture); PREP (Preparation)

(monomer; preparation of fluorine-containing polymerizable styrene monomers)

RN 2386-82-5 CAPLUS

CN Benzenemethanol, 4-ethenyl- α,α -bis(trifluoromethyl)- (9CI)
(CA INDEX NAME)



L9 ANSWER 2 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:1012045 CAPLUS

DN 142:13671

TI Photosensitive resin composition

IN Kanna, Shinichi; Mizutani, Kazuyoshi; Sasaki, Tomoya

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 133 pp.

CODEN: EPXXDW

DT Patent

LA English

FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1480079	A2	20041124	EP 2004-19923	20030606
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
	JP 2004012898	A2	20040115	JP 2002-167393	20020607
	JP 2004029111	A2	20040129	JP 2002-181384	20020621
	JP 2004029136	A2	20040129	JP 2002-181588	20020621
	EP 1376232	A1	20040102	EP 2003-12226	20030606
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
PRAI	JP 2002-167393	A	20020607		
	JP 2002-181384	A	20020621		
	JP 2002-181588	A	20020621		
	EP 2003-12226	A3	20030606		

IT **485390-42-9P**

RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

10/600,510

(photosensitive resin composition)

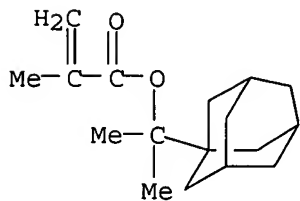
RN 485390-42-9 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-methyl-1-tricyclo[3.3.1.1^{3,7}]dec-1-ylethyl ester, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol and 1-ethenyl-4-(1-methoxyethoxy)benzene (9CI) (CA INDEX NAME)

CM 1

CRN 279218-76-7

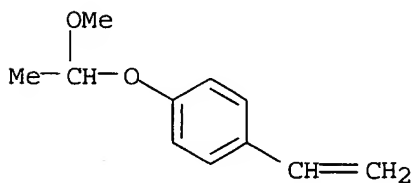
CMF C17 H26 O2



CM 2

CRN 151189-10-5

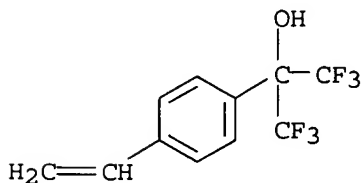
CMF C11 H14 O2



CM 3

CRN 2386-82-5

CMF C11 H8 F6 O



L9 ANSWER 3 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2004:5239 CAPLUS

DN 140:67635

TI Photosensitive resin composition

IN Kanna, Shinichi; Mizutani, Kazuyoshi; Sasaki, Tomoya

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 136 pp.

CODEN: EPXXDW

10/600,510

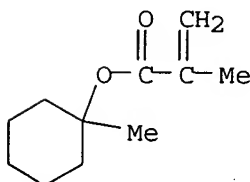
DT Patent
LA English
FAN.CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1376232	A1	20040102	EP 2003-12226	20030606
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
	JP 2004012898	A2	20040115	JP 2002-167393	20020607
	JP 2004029111	A2	20040129	JP 2002-181384	20020621
	JP 2004029136	A2	20040129	JP 2002-181588	20020621
	US 2004009430	A1	20040115	US 2003-455459	20030606
	EP 1480079	A2	20041124	EP 2004-19923	20030606
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK				
PRAI	JP 2002-167393	A	20020607		
	JP 2002-181384	A	20020621		
	JP 2002-181588	A	20020621		
	EP 2003-12226	A3	20030606		
IT	485390-41-8P				
	RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)				
	(microlithog. photosensitive resin composition containing)				
RN	485390-41-8 CAPLUS				
CN	2-Propenoic acid, 2-methyl-, 1-methylcyclohexyl ester, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol and 2-(4-ethenylphenoxy)tetrahydro-2H-pyran (9CI) (CA INDEX NAME)				

CM 1

CRN 76392-14-8

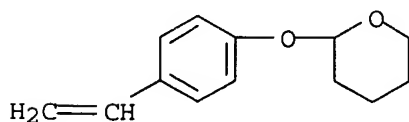
CMF C11 H18 O2



CM 2

CRN 65409-15-6

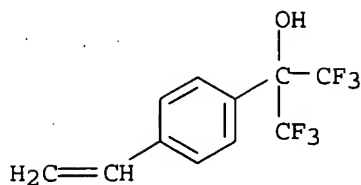
CMF C13 H16 O2



CM 3

CRN 2386-82-5

CMF C11 H8 F6 O



RE.CNT 5 THERE ARE 5 CITED REFERENCES AVAILABLE FOR THIS RECORD
ALL CITATIONS AVAILABLE IN THE RE FORMAT

L9 ANSWER 4 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2003:945845 CAPLUS
DN 140:21261
TI Photosensitive resin composition for photolithography
IN Kanna, Shinichi; Mizutani, Kazuyoshi; Sasaki, Tomoya
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 71 pp.
CODEN: JKXXAF

DT Patent
LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003344994	A2	20031203	JP 2002-154391	20020528
PRAI	JP 2002-154391		20020528		

IT **430437-18-6P**

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(photoresist composition containing acid-decomposable polymer, acid generator,
and F-containing solvent)

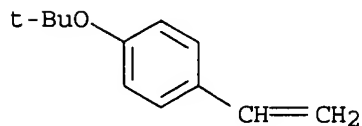
RN 430437-18-6 CAPLUS

CN Benzenemethanol, 4-ethenyl- α,α -bis(trifluoromethyl)-, polymer
with 1-(1,1-dimethylethoxy)-4-ethenylbenzene (9CI) (CA INDEX NAME)

CM 1

CRN 95418-58-9

CMF C12 H16 O

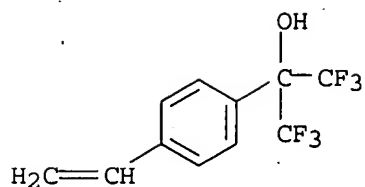


CM 2

CRN 2386-82-5

CMF C11 H8 F6 O

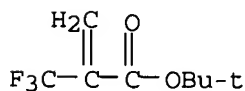
10/600,510



L9 ANSWER 5 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2003:369197 CAPLUS
DN 138:393073
TI Positive-working photoresist composition containing fluoro-substituted nitrogen compound
IN Fujimori, Toru; Kanna, Shinichi
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 53 pp.
CODEN: JKXXAF
DT Patent
LA Japanese
FAN.CNT 1

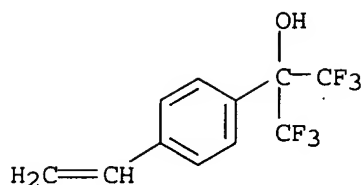
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003140349	A2	20030514	JP 2001-339439	20011105
PRAI	JP 2001-339439		20011105		

IT **370866-13-0P**
RL: PNU (Preparation, unclassified); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(pos. photoresist containing F-containing alkali-soluble polymer, acid generator,
and F-containing nitrogen compound)
RN 370866-13-0 CAPLUS
CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1,1-dimethylethyl ester, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol (9CI)
(CA INDEX NAME)
CM 1
CRN 105935-24-8
CMF C8 H11 F3 O2



CM 2
CRN 2386-82-5
CMF C11 H8 F6 O

10/600,510



L9 ANSWER 6 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2003:152372 CAPLUS
DN 138:212786
TI Vacuum UV-sensitive resin composition containing ionic compound reactive
towards acid
IN Kanna, Shinichi; Mizutani, Kazuyoshi
PA Fuji Photo Film Co., Ltd., Japan
SO Jpn. Kokai Tokkyo Koho, 66 pp.
CODEN: JKXXAF

DT Patent
LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003057826	A2	20030228	JP 2001-250535	20010821
PRAI	JP 2001-250535		20010821		

IT 485390-41-8P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material
use); PREP (Preparation); USES (Uses)

(resin; Vacuum UV-sensitive resin composition containing ionic compound
reactive towards acid)

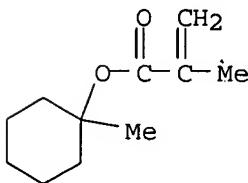
RN 485390-41-8 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 1-methylcyclohexyl ester, polymer with
4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol and
2-(4-ethenylphenoxy)tetrahydro-2H-pyran (9CI) (CA INDEX NAME)

CM 1

CRN 76392-14-8

CMF C11 H18 O2

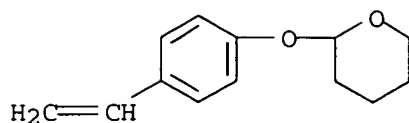


CM 2

CRN 65409-15-6

CMF C13 H16 O2

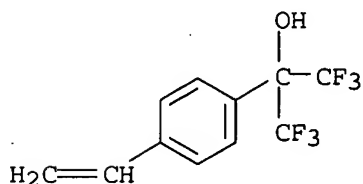
10/600,510



CM 3

CRN 2386-82-5

CMF C11 H8 F6 O



L9 ANSWER 7 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2003:35187 CAPLUS

DN 138:98199

TI Positive-working vacuum UV-sensitive photoresist material composition containing specific resin

IN Kanna, Shinichi; Mizutani, Kazuyoshi

PA Fuji Photo Film Co., Ltd., Japan

SO Jpn. Kokai Tokkyo Koho, 39 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003015298	A2	20030115	JP 2001-202241	20010703
PRAI	JP 2001-202241		20010703		

IT 485390-41-8P

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(resin; pos.-working vacuum UV-sensitive photoresist material composition containing specific resin)

RN 485390-41-8 CAPLUS

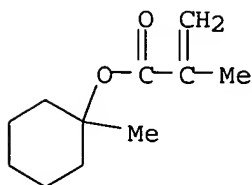
CN 2-Propenoic acid, 2-methyl-, 1-methylcyclohexyl ester, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol and 2-(4-ethenylphenoxy)tetrahydro-2H-pyran (9CI) (CA INDEX NAME)

CM 1

CRN 76392-14-8

CMF C11 H18 O2

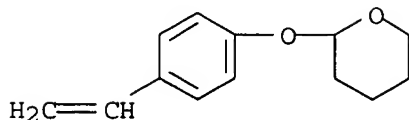
10/600,510



CM 2

CRN 65409-15-6

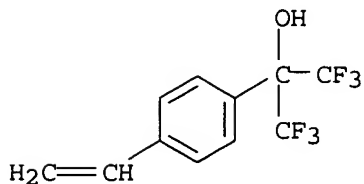
CMF C13 H16 O2



CM 3

CRN 2386-82-5

CMF C11 H8 F6 O



L9 ANSWER 8 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2003:470377 CAPLUS

DN 139:44224

TI Positive-working resist composition containing specific fluorine group-containing resin

IN Kanna, Shinichi; Mizutani, Kazuyoshi; Kodama, Kunihiro; Sasaki, Tomoya

PA Fuji Photo Film Co., Ltd., Japan

SO Eur. Pat. Appl., 80 pp.

CODEN: EPXXDW

DT Patent

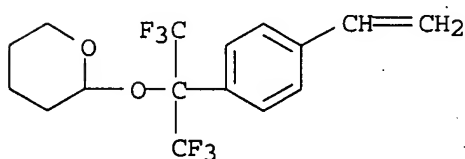
LA English

FAN.CNT 1

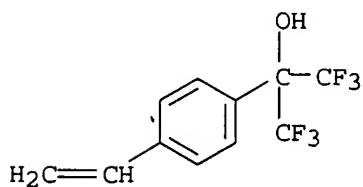
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	EP 1319981	A2	20030618	EP 2002-27667	20021212
	EP 1319981	A3	20030723		
	R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, SK				
	US 2003194650	A1	20031016	US 2002-317110	20021212
	JP 2003241386	A2	20030827	JP 2002-362629	20021213
PRAI	JP 2001-380104	A	20011213		

10/600,510

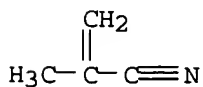
JP 2001-380105 A 20011213
IT 430437-03-9P
RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(fluorine group-containing resin)
RN 430437-03-9 CAPLUS
CN 2-Propenenitrile, 2-methyl-, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol and 2-[1-(4-ethenylphenyl)-2,2,2-trifluoro-1-(trifluoromethyl)ethoxy]tetrahydro-2H-pyran (9CI) (CA INDEX NAME)
CM 1
CRN 430437-02-8
CMF C16 H16 F6 O2



CM 2
CRN 2386-82-5
CMF C11 H8 F6 O



CM 3
CRN 126-98-7
CMF C4 H5 N



L9 ANSWER 9 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN
AN 2002:392162 CAPLUS
DN 136:409022
TI Positive resist composition
IN Aoi, Toshiaki; Yasunami, Shoichiro; Mizutani, Kazuyoshi; Kanna, Shinichi
PA Fuji Photo Film Co., Ltd., Japan
SO U.S. Pat. Appl. Publ., 56 pp.
CODEN: USXXCO

10/600,510

DT Patent
LA English
FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 2002061464	A1	20020523	US 2001-961281	20010925
	US 6852467	B2	20050208		
	JP 2002333715	A2	20021122	JP 2001-202298	20010703
	TW 528931	B	20030421	TW 2001-90123599	20010925
PRAI	JP 2000-292537	A	20000926		
	JP 2000-379284	A	20001213		
	JP 2001-62158	A	20010306		
	JP 2001-202298	A	20010703		

IT **430437-01-7P**

RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
(fluorine group-containing resin for pos. resist composition)

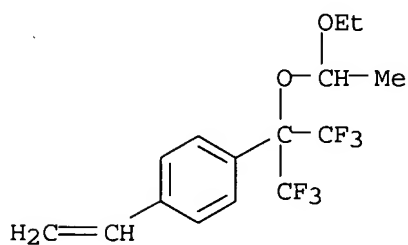
RN 430437-01-7 CAPLUS

CN 2-Propenenitrile, 2-methyl-, polymer with 4-ethenyl- α,α -bis(trifluoromethyl)benzenemethanol and 1-ethenyl-4-[1-(1-ethoxyethoxy)-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]benzene (9CI) (CA INDEX NAME)

CM 1

CRN 430437-00-6

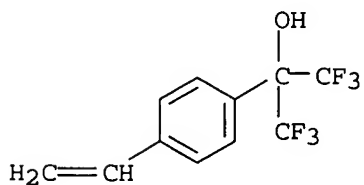
CMF C15 H16 F6 O2



CM 2

CRN 2386-82-5

CMF C11 H8 F6 O

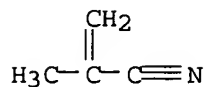


CM 3

CRN 126-98-7

CMF C4 H5 N

10/600,510



L9 ANSWER 10 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN

AN 2002:847803 CAPLUS

DN 137:360305

TI Polymers with fluorinated styrene-based mer units, their positive resist materials, and their patterning

IN Hatakeyama, Jun; Harada, Yuji; Watanabe, Atsushi; Sasako, Masaru; Endo, Masataka; Kishimura, Shinji; Otani, Mitsutaka; Miyazawa, Satoru; Tsutsumi, Kentaro; Maeda, Kazuhiko

PA Shin-Etsu Chemical Industry Co., Ltd., Japan; Matsushita Electric Industrial Co., Ltd.; Central Glass Co., Ltd.

SO Jpn. Kokai Tokkyo Koho, 28 pp.

CODEN: JKXXAF

DT Patent

LA Japanese

FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2002322217	A2	20021108	JP 2001-128529	20010426
PRAI	JP 2001-128529		20010426		

IT **474088-23-8P**

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(polymers with fluorinated styrene-based mer units, their pos. DUV resist materials, and their patterning)

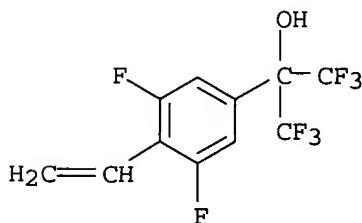
RN 474088-23-8 CAPLUS

CN 2-Propenoic acid, 1,1-dimethylethyl ester, polymer with 4-ethenyl-3,5-difluoro- α,α -bis(trifluoromethyl)benzenemethanol (9CI) (CA INDEX NAME)

CM 1

CRN 474088-22-7

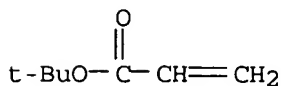
CMF C11 H6 F8 O



CM 2

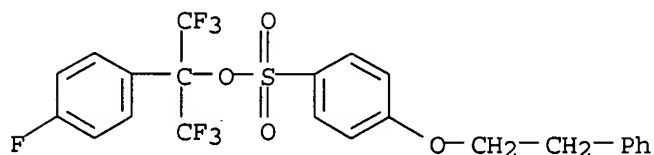
CRN 1663-39-4

CMF C7 H12 O2



L9 ANSWER 11 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN
 AN 1995:441113 CAPLUS
 DN 122:201235
 TI Sulfonic acid esters, their production and photosensitive compositions containing them.
 IN Pawlowski, Georg; Spiess, Walter; Roeschert, Horst; Appel, Wolfgang; Herr, Walter
 PA Hoechst A.-G., Germany
 SO Ger. Offen., 26 pp.
 CODEN: GWXXBX
 DT Patent
 LA German
 FAN. CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	DE 4302681	A1	19940804	DE 1993-4302681	19930201
	WO 9418606	A1	19940818	WO 1993-EP2701	19931004
	W: JP, KR, US				
	RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE				
	EP 681713	A1	19951115	EP 1993-921907	19931004
	EP 681713	B1	19981118		
	R: DE, FR, GB, IT				
	JP 08506908	T2	19960723	JP 1993-510420	19931004
	JP 3348789	B2	20021120	JP 1994-510420	19931004
	US 5716756	A	19980210	US 1995-424532	19950530
PRAI	DE 1993-4302681	A	19930201		
	WO 1993-EP2701	W	19931004		
OS	MARPAT 122:201235				
IT	161759-14-4				
	RL: MOA (Modifier or additive use); USES (Uses)				
	(photoacid generator)				
RN	161759-14-4 CAPLUS				
CN	Benzenesulfonic acid, 4-(2-phenylethoxy)-, 2,2,2-trifluoro-1-(4-fluorophenyl)-1-(trifluoromethyl)ethyl ester (9CI) (CA INDEX NAME)				

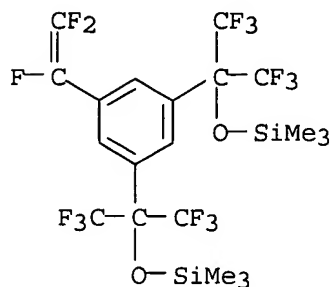


L9 ANSWER 12 OF 12 CAPLUS COPYRIGHT 2005 ACS on STN
 AN 1991:558597 CAPLUS
 DN 115:158597
 TI The synthesis and attempted polymerization of an α,β,β -trifluorostyrene disubstituted by hexafluoro-2-propyl groups
 AU Sprague, Lee G.; Snow, Arthur W.; Griffith, James R.
 CS Chem. Div., Nav. Res. Lab., Washington, DC, 20375-5000, USA
 SO Journal of Fluorine Chemistry (1991), 52(3), 301-6
 CODEN: JFLCAR; ISSN: 0022-1139
 DT Journal
 LA English
 OS CASREACT 115:158597
 IT 136365-60-1P
 RL: SPN (Synthetic preparation); PREP (Preparation)
 (preparation and attempted polymerization of)

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RN 136365-60-1 CAPLUS

CN Silane, [[5-(trifluoroethenyl)-1,3-phenylene]bis[[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene]oxy]]bis[trimethyl- (9CI) (CA INDEX NAME)



=> log hold

COST IN U.S. DOLLARS

SINCE FILE	TOTAL
ENTRY	SESSION
48.57	372.79

FULL ESTIMATED COST

SESSION WILL BE HELD FOR 60 MINUTES

STN INTERNATIONAL SESSION SUSPENDED AT 14:15:59 ON 18 FEB 2005

Connecting via Winsock to STN

Welcome to STN International! Enter x:x

LOGINID:SSSPTA1204RXW

PASSWORD:

***** RECONNECTED TO STN INTERNATIONAL *****
SESSION RESUMED IN FILE 'CAPLUS' AT 14:31:44 ON 18 FEB 2005
FILE 'CAPLUS' ENTERED AT 14:31:44 ON 18 FEB 2005
COPYRIGHT (C) 2005 AMERICAN CHEMICAL SOCIETY (ACS)

COST IN U.S. DOLLARS

SINCE FILE	TOTAL
ENTRY	SESSION
48.57	372.79

FULL ESTIMATED COST

=> D HIS

(FILE 'HOME' ENTERED AT 14:07:10 ON 18 FEB 2005)

FILE 'STNGUIDE' ENTERED AT 14:07:26 ON 18 FEB 2005

FILE 'REGISTRY' ENTERED AT 14:07:46 ON 18 FEB 2005

L1 STRUCTURE UPLOADED
L2 29 S L1
L3 669 S L1 FUL
L4 STRUCTURE UPLOADED
L5 QUE L4
L6 23 S L5
L7 345 S L5 FUL

FILE 'CAPLUS' ENTERED AT 14:10:45 ON 18 FEB 2005

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L8 12 S L3 AND L7
L9 12 DUP REM L8 (0 DUPLICATES REMOVED)

=> s l3/prep
 255 L3
 3264165 PREP/RL
L10 131 L3/PREP
 (L3 (L) PREP/RL)

=> file save
'SAVE' IS NOT A VALID FILE NAME
SESSION CONTINUES IN FILE 'CAPLUS'
Enter "HELP FILE NAMES" at an arrow prompt (=>) for a list of files that are available. If you have requested multiple files, you can specify a corrected file name or you can enter "IGNORE" to continue accessing the remaining file names entered.

=> save
ENTER L#, L# RANGE, ALL, OR (END):11-110
ENTER NAME OR (END):styrene
STYRENE IS NOT A VALID SAVED NAME
Enter the name you wish to use for the saved query, answer set, or L-number list. The name must:

1. Begin with a letter,
2. Have 1-12 characters,
3. Contain only letters (A-Z) and numbers (0-9),
4. End with /Q for a query (search profile, structure, or screen set), /A for an answer set, or /L for an L-number list.
5. Not already be in use as a saved name,
6. Not be END, SAV, SAVE, SAVED
7. Not have the form of an L-number (Lnnn).

ENTER NAME OR (END):styrene/a
L1-L10 IS NOT ALLOWED WITH ANSWER SET NAME: STYRENE/A
Selectively saving L-numbers to an L-number list can only be saved to a name ending with /L.

=> styrene/l
STYRENE IS NOT A RECOGNIZED COMMAND
The previous command name entered was not recognized by the system.
For a list of commands available to you in the current file, enter "HELP COMMANDS" at an arrow prompt (=>).

=> help commands
Enter one of these commands at the arrow prompt (=>).

ACTIVATE ----- Assign L#s to saved query or answer set.
ANALYZE ----- Build expand terms from answer fields.
ARCHIVE ----- Purchase rights for archiving.
DELETE ----- Delete saved or current session items.
DISPLAY ----- Display saved or current session items.
DUPLICATE ---- Determine duplicate answers
EDIT ----- Modify the text of an E-number entry.
EXPAND ----- Look at the index around a term.
FILE ----- Specify the search and display file.
FOCUS ----- Rank answers in order of relevancy.
FSEARCH ----- Find records from given patent family(s)
FSORT ----- Sort patent records by patent family
HELP ----- For help on how to use the system.
INDEX ----- Specify the Index environment.
LOGOFF ----- End the online session.
NEWS ----- Display current news about the system.

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ORDER ----- Order an original document or copy.
PRINT ----- Print answers offline.
QUERY ----- Define a search question (query).
REDISTRIBUTE - Purchase rights for redistribution.
SAVE ----- Save an L-numbered query or answer set.
SDI ----- Request searches be run on file updates.
SEARCH ----- Perform a search.
SELECT ----- Build expand terms from answer fields.
SET ----- Set terminal and interaction options.
SORT ----- Sort Answers of an L-number list
TABULATE ----- Analyze SmartSELECT L-number data.
TRANSFER ----- Extract terms from answers and search.
? ----- The same as HELP.
Enter one of these commands at the arrow prompt (=>).

For more detailed information about a command, enter HELP followed by the command name at an arrow prompt.

Example: => HELP SEARCH

For information on entering multiple commands at a single arrow prompt, enter HELP COMMAND STACKING.

=> save l10
ENTER NAME OR (END):styrene/a
ANSWER SET L10 HAS BEEN SAVED AS 'STYRENE/A'

=> log y

COST IN U.S. DOLLARS	SINCE FILE ENTRY	TOTAL SESSION
FULL ESTIMATED COST	54.51	378.73

STN INTERNATIONAL LOGOFF AT 14:36:52 ON 18 FEB 2005

Connecting via Winsock to STN

Welcome to STN International! Enter x:x

LOGINID:SSSPTA1204RXW

PASSWORD:
TERMINAL (ENTER 1, 2, 3, OR ?):2

* * * * * Welcome to STN International * * * * *

NEWS	1	Web Page URLs for STN Seminar Schedule - N. America
NEWS	2	"Ask CAS" for self-help around the clock
NEWS	3	SEP 01 New pricing for the Save Answers for SciFinder Wizard within STN Express with Discover!
NEWS	4	OCT 28 KOREAPAT now available on STN
NEWS	5	NOV 30 PHAR reloaded with additional data
NEWS	6	DEC 01 LISA now available on STN
NEWS	7	DEC 09 12 databases to be removed from STN on December 31, 2004
NEWS	8	DEC 15 MEDLINE update schedule for December 2004
NEWS	9	DEC 17 ELCOM reloaded; updating to resume; current-awareness